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Simon Min Sze (Chinese: 施敏; pinyin: Sh ǎ m ĩn; born 1936) is a Chinese-American electrical engineer.He is best known for inventing the floating-gate MOSFET with Dawon Kahng in 1967.. Biography. Sze was born in Nanjing, China, and grew up in Taiwan.After graduating from the National Taiwan University in 1957, he received a master’s degree from the University of Washington in 1960 and a ...

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This is a superb state-of-the-art collection of contributed readings by nationally recognized authorities in VLSI technology. The emphasis of this text is on fabrication.

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Offers a basic, up-to-date introduction to semiconductor fabrication technology, including both the theoretical and practical aspects of all major steps in the fabrication sequence Presents comprehensive coverage of process sequences Introduces readers to modern simulation tools Addresses the practical aspects of integrated circuit fabrication Clearly explains basic processing theory

The awaited revision of Semiconductor Devices: Physics and Technology offers more than 50% new or revised material that reflects a multitude of important discoveries and advances in device physics and integrated circuit processing. Offering a basic introduction to physical principles of modern semiconductor devices and their advanced fabrication technology, the third edition presents students with theoretical and practical aspects of every step in device characterizations and fabrication, with an emphasis on integrated circuits. Divided into three parts, this text covers the basic properties of semiconductor materials, emphasizing silicon and gallium arsenide; the physics and characteristics of semiconductor devices bipolar, unipolar special microwave and photonic devices; and the latest processing technologies, from crystal growth to lithographic pattern transfer.

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